

Amendment and Response

Serial No.: 09/560,268

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For: COMPOSITION FOR SELECTIVELY ETCHING AGAINST COBALT SILICIDE (As Amended)

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95. (New) The etching composition according to claim 94, wherein the mineral acid is HCl and the peroxide is hydrogen peroxide.

96. (New) The etching composition according to claim 94, wherein the ratio is in a range of about 1:1:25 (mineral acid:peroxide:deionized water) to about 1:1:10 (mineral acid:peroxide:deionized water).
